



**(10) International Publication Number**  
**WO 2011/064154 A2**

**(43) International Publication Date**  
**3 June 2011 (03.06.2011)**

## PCT

- (51) **International Patent Classification:** Not classified

(21) **International Application Number:** PCT/EP2010/067874

(22) **International Filing Date:** 22 November 2010 (22.11.2010)

(25) **Filing Language:** English

(26) **Publication Language:** English

(30) **Priority Data:** 61/264,705 27 November 2009 (27.11.2009) US

(71) **Applicant (for all designated States except US):** **BASF SE** [DE/DE]; 67056 Ludwigshafen (DE).

(72) **Inventors; and**

(75) **Inventors/Applicants (for US only):** **RÖGER-GÖPFERT, Cornelia** [DE/DE]; Kastanienweg 49-51, 68723 Schwetzingen (DE). **RAETHER, Roman Benedikt** [DE/DE]; Carl-Schalk-Str. 27, 67346 Speyer (DE). **MAYER, Dieter** [DE/DE]; Zerninstr. 15 E, 64297 Darmstadt (DE). **EMNET, Charlotte** [DE/DE]; Sonnenbühl 9, 70597 Stuttgart (DE). **ARNOLD, Marco** [DE/DE]; Sofienstraße 23, 69115 Heidelberg (DE).

(74) **Common Representative:** **BASF SE**; 67056 Ludwigshafen (DE).

(81) **Designated States (unless otherwise indicated, for every kind of national protection available):** AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) **Designated States (unless otherwise indicated, for every kind of regional protection available):** ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

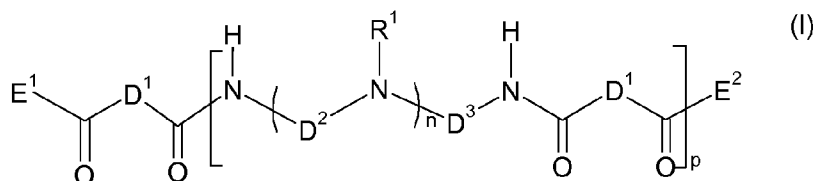
**Published:**

— without international search report and to be republished upon receipt of that report (Rule 48.2(g))

**Published:**

— without international search report and to be republished upon receipt of that report (Rule 48.2(g))

**(54) Title:** COMPOSITION FOR METAL ELECTROPLATING COMPRISING LEVELING AGENT



**(S7) Abstract:** A composition comprising a source of metal ions and at least one additive comprising at least one polyaminoamide represented by formula (I) or derivatives of a polyaminoamide of formula (I) obtainable by complete or partial protonation, N-quarternisation or acylation.